

Title (en)

LOW-VOLTAGE PUNCH-THROUGH TRANSIENT SUPPRESSOR EMPLOYING A DUAL-BASE STRUCTURE

Title (de)

DURCHBRUCHTRANSIERTER NIEDERSpannungs-UNTERDRÜCKER MIT ZWEISCHICHTIGER BASIS

Title (fr)

LIMITEUR BASSE TENSION DE SURTENSION DE CLAQUAGE UTILISANT UNE STRUCTURE DE BASE DOUBLE

Publication

**EP 0840943 A1 19980513 (EN)**

Application

**EP 96917059 A 19960603**

Priority

- US 9608545 W 19960603
- US 49707995 A 19950630

Abstract (en)

[origin: WO9702606A1] A punch-through diode transient suppression device has a base region of varying doping concentration to improve leakage and clamping characteristics. The punch-through diode includes a first region comprising an n+ region (12), a second region comprising a p- region abutting the first region, a third region comprising a p+ region (16) abutting the second region, and a fourth region comprising an n+ region (18) abutting the third region. The peak dopant concentration of the n+ layers should be about  $1.5 \times 10^{18} \text{ cm}^{-3}$ , the peak dopant concentration of the p+ layer should be between about 1 to about 5 times the peak concentration of the n+ layer, and the dopant concentration of the p- layer should be between about  $0.5 \times 10^{14} \text{ cm}^{-3}$  and about  $1.0 \times 10^{17} \text{ cm}^{-3}$ . The junction depth of the fourth (n+) region (18) should be greater than about 0.3  $\mu\text{m}$ . The thickness of the third (p+) region (16) should be between about 0.3  $\mu\text{m}$  and about 2.0  $\mu\text{m}$ , and the thickness of the second (p-) region should be between about 0.5  $\mu\text{m}$  and about 5.0  $\mu\text{m}$ .

IPC 1-7

**H01L 29/861**; **H01L 29/866**

IPC 8 full level

**H01L 29/861** (2006.01); **H01L 29/866** (2006.01)

CPC (source: EP US)

**H01L 29/861** (2013.01 - EP US); **H01L 29/8618** (2013.01 - EP US); **H01L 29/866** (2013.01 - EP US)

Citation (search report)

See references of WO 9702606A1

Designated contracting state (EPC)

DE FI

DOCDB simple family (publication)

**WO 9702606 A1 19970123**; DE 69625815 D1 20030220; DE 69625815 T2 20031030; EP 0840943 A1 19980513; EP 0840943 B1 20030115; JP 3295092 B2 20020624; JP H11509041 A 19990803; US 5880511 A 19990309; US 6015999 A 20000118

DOCDB simple family (application)

**US 9608545 W 19960603**; DE 69625815 T 19960603; EP 96917059 A 19960603; JP 50513397 A 19960603; US 3992698 A 19980316; US 49707995 A 19950630